



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of

CHEN et al.

Atty. Ref.: 2476-37; Confirmation No. 2846

Appl. No. 10/730,381

TC/A.U. 2815

Filed: 09 December 2003

Examiner: Jackson Jr., Jerome

For: PROGRAMMABLE PHOTOLITHOGRAPHIC MASK BASED ON SEMICONDUCTOR
NANO-PARTICLE OPTICAL MODULATORS

* * * * *

May 10, 2005

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

RESTRICTION REQUIREMENT

Responsive to the Official Action of December 10, 2004 and the requirement for restriction presented in it, applicants elect, with traverse, the subject matter of Group II, that is claims 20-39 directed to a process of manufacture, classified in class 438, subclass 57.

An examination on the merits is awaited.

Respectfully submitted,

NIXON & VANDERHYE P.C.

By: 

Robert W. Faris
Reg. No. 31,352

RWF:ej
901 North Glebe Road, 11th Floor
Arlington, VA 22203-1808
Telephone: (703) 816-4000
Facsimile: (703) 816-4100